

| L Number | Hits  | Search Text  | DB                       | Time stamp       |
|----------|-------|--|--------------------------|------------------|
| 1        | 52259 | (mask or reticle or original) same (pinhole or hole)   | USPAT; EPO; JPO; DERWENT | 2002/09/09 09:25 |
| 2        | 23007 | (mask or reticle or original) near8 (pinhole or hole)  | USPAT; EPO; JPO; DERWENT | 2002/09/09 09:26 |
| 3        | 11092 | ((mask or reticle or original) near8 (pinhole or hole)) and (substrate or wafer or target)   | USPAT; EPO; JPO; DERWENT | 2002/09/09 09:28 |
| 4        | 1565  | ((((mask or reticle or original) near8 (pinhole or hole)) and (substrate or wafer or target)) and (355/\$.ccls. or 356/\$.ccls. or 250/\$.ccls. or 430/\$.ccls.)   | USPAT; EPO; JPO; DERWENT | 2002/09/09 09:29 |
| 5        | 119   | ((((mask or reticle or original) near8 (pinhole or hole)) and (substrate or wafer or target)) and (355/\$.ccls. or 356/\$.ccls. or 250/\$.ccls. or 430/\$.ccls.)) and (((sens\$4 or detect\$4 or measu\$4) near5 (intensity or exposure)) same (wafer or substrate)) | USPAT; EPO; JPO; DERWENT | 2002/09/09 09:59 |